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A	PPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
	10/055,608	01/23/2002	Wolfgang Singer	637.0017USU	6642	
	75	90 03/03/2003				
	Charles N.J. R			EXAM	EXAMINER	
	Ohlandt, Greeley, Ruggiero & Perle, L.L.P. 10th Floor		L.P.	PRITCHETT	PRITCHETT, JOSHUA L	
* **	One Landmark Stamford, CT		€ • · · · · · · · · · · · · · · · · · ·	ART UNIT	~PAPER NUMBER	
	J	00,01 2002		2872		
				DATE MAILED: 03/03/2003	3	

Please find below and/or attached an Office communication concerning this application or proceeding.

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١,		Application No.	Applicant(s)			
Office Action Summary		10/055,608	SINGER ET AL.			
	Onice Action Summary	Examiner	Art Unit			
	The MAIL DIO DATE AND	Joshua L Pritchett	2872			
Period fo	The MAILING DATE of this communication apported in the communication apport.	pears on the cover sheet with the	correspondence address			
- Exter after - If the - If NO - Failur - Any re	ORTENED STATUTORY PERIOD FOR REPL' MAILING DATE OF THIS COMMUNICATION. nsions of time may be available under the provisions of 37 CFR 1.13 SIX (6) MONTHS from the mailing date of this communication. p period for reply specified above is less than thirty (30) days, a reply p operiod for reply is specified above, the maximum statutory period re to reply within the set or extended period for reply will, by statute, reply received by the Office later than three months after the mailing ad patent term adjustment. See 37 CFR 1.704(b).	36(a). In no event, however, may a reply be till y within the statutory minimum of thirty (30) day will apply and will expire SIX (6) MONTHS from	mely filed ys will be considered timely. the mailing date of this communication.			
1)🖂	Responsive to communication(s) filed on 23 J	anuary 2002				
2a)		s action is non-final.				
3) Disposition	25)25 This dollar is non-linal.					
4)🖂	Claim(s) 26-51 is/are pending in the application	n.				
4	4a) Of the above claim(s) is/are withdraw	n from consideration.				
	Claim(s) is/are allowed.					
6)⊠	Claim(s) <u>26-28,31-33,37,41-48,50 and 51</u> is/are	e rejected.	·			
	Claim(s) <u>29,30,34-36,38-40 and 49</u> is/are object					
	Claim(s) are subject to restriction and/or					
Application	on Papers					
9) <u></u> ⊤	he specification is objected to by the Examiner.					
10)⊠ T	he drawing(s) filed on 23 January 2002 is/are:	a)⊠ accepted or b)☐ objected to b	by the Examiner.			
	Applicant may not request that any objection to the	drawing(s) be held in abeyance. Se	ee 37 CFR 1.85(a)			
11) 🔲 T	he proposed drawing correction filed on	is: a) ☐ approved b) ☐ disappro	ved by the Examiner.			
	If approved, corrected drawings are required in repl					
12)∏ T	he oath or declaration is objected to by the Exa	miner.				
Priority ur	nder 35 U.S.C. §§ 119 and 120					
13)⊠- A	Acknowledgment-is-made-of a-claim for-foreign-	priority-under-35-U-S-G- § 1-19(a)	-(d)-or-(f)			
	〗All b)☐ Some * c)☐ None of:	,				
1	1. Certified copies of the priority documents	have been received.				
2	2. Certified copies of the priority documents		on No.			
	B. Copies of the certified copies of the priorit application from the International Bure	y documents have been received	d in this National Stage			
	ee the attached detailed Office action for a list of					
14)LJ AC	knowledgment is made of a claim for domestic	priority under 35 U.S.C. § 119(e)	(to a provisional application).			
ا (م 15)∐ Ac Attachment(s	The translation of the foreign language provicknowledgment is made of a claim for domestic	isional application has been rece priority under 35 U.S.C. §§ 120 a	eived. and/or 121.			
1) Notice (2) Notice (3) Informa	of References Cited (PTO-892) of Draftsperson's Patent Drawing Review (PTO-948) ation Disclosure Statement(s) (PTO-1449) Paper No(s) <u>4</u> .	4) Interview Summary (5) Notice of Informal Pa 6) Other:	(PTO-413) Paper No(s) atent Application (PTO-152)			
S. Patent and Trad TO-326. (Rev.		on Summary	Part of Paper No. 9			

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DETAILED ACTION

Claim Objections

Claims 30, 42, 45 and 48-49 are objected to because of the following informalities: the claims include reference to "said light source" this structure limitation lacks antecedent basis.

Appropriate correction is required.

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty-in-the English language.

Claims 26, 32-33, 37, 41-43, 48 and 50-51 are rejected under 35 U.S.C. 102(e) as being anticipated by Chapman (US 6,186,632).

Regarding claim 26, Chapman discloses a collector for guiding light of wavelength less than or equal to 193 nm onto a plane (col. 4 lines 22-25). Extreme Ultraviolet lithography deals with wavelengths less than 193 nm. Chapman further discloses a first and second mirror shell

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for receiving a first and second ring aperture section of said light and irradiating a first and second planar ring section of said plane with a first and second irradiance (Fig. 6, 608).

Chapman further discloses the first and second mirror shells are rotationally symmetrical and concentrically arranged around a common axis of rotation (Fig. 6, 608). Chapman further discloses the first and second ring apertures do not overlap one another (Fig. 6, 608). Chapman further discloses the first ring section substantially abuts the second ring section (Fig. 6, 608). Chapman further teaches the first irradiance is approximately equal to the second irradiance. Chapman makes no reference to altering the incident light in any way other than to change the direction (col. 7 lines 3-15) therefore the intensity of the light exiting both ring sections would be the same.

Regarding claim 28, Chapman discloses the first mirror shell is an inner shell and the second mirror shell is an outer shell (Fig. 6, 608). Chapman discloses that a point used to define the location of the second shell is further from the axis of rotation than a point used to define the location of the first shell (Fig. 6, 608).

Regarding claim 32, Chapman discloses the first and second mirror shell are each a ring-shaped segment of an aspherical object (col. 6 lines 61-63).

Regarding claim 33, Chapman discloses the first and second mirror shells are formed in an ellipsoid (col. 6 lines 61-63).

Regarding claim 37, Chapman discloses wherein the first and second ring aperture segments are separated by a gap (Fig. 6, 608)

Regarding claim 41, Chapman discloses wherein the first and second mirror shells are two of a plurality of mirror shells comprising at least three mirror shells (Fig. 6, 608).

Regarding claim 42, Chapman discloses the light source emits rays that impinge with the angle of incident of less than 20 degrees to surface tangents of the first and second mirror shells (col. 6 line 66 – col. 7 line 2).

Regarding claim 43, Chapman discloses an illumination system using the collector (Fig. 6).

Regarding claim 48, Chapman discloses an illumination system wherein the system comprises a second plan conjugated to the light source between the collector and the first plane in which an intermediate image of the light source is formed (Fig. 6, 610).

Regarding claim 50, Chapman discloses an EUV projection system with a mask and a projection objective (col. 4 lines 33-45).

Regarding claim 51, Chapman discloses a process for producing a microelectronic device comprising EUV projection exposure (col. 4 lines 33-45).

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

⁽a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

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Claims 27 and 31 are rejected under 35 U.S.C. 103(a) as being unpatentable over Chapman in view of Amos (US 5,369,511).

Chapman teaches the invention as claimed but lacks reference to the first and second shells having different dimensions in the direction of the rotational axis. Amos teaches the first and second shells having different dimensions in the direction of the rotational axis (Fig. 20). It would be within the skill of one ordinarily trained in the art to make each of the shells larger or smaller depending on the desired design. It would have been obvious to a person of ordinary skill in the art to have the Chapman shells have different dimensions in the direction of the axis of rotation as taught by Amos for the purpose of having better defined rings on the image plane.

Claims 44-47 are rejected under 35 U.S.C. 103(a) as being unpatentable over Chapman in view of Schultz (US 6,198,793).

Regarding claims 44 and 45, Chapman teaches the invention as claimed but lacks reference to the use of raster elements. Schultz teaches the use of raster elements in EUV lithography (col. 2 lines 39-40). It would have been obvious to a person of ordinary skill in the art at the time the invention was made to have the Chapman collector contain the raster elements taught by Schultz for the purpose of providing extra versatility to the EUV lithography design.

Regarding claim 46, Chapman teaches the illumination system has a second optical element for imaging (Fig. 6, 610).

Regarding claim 47, Chapman teaches the second optical element is used for field shaping (col. 7 lines 7-8).

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Allowable Subject Matter

Claims 29-30, 34-36, 38-40 and 49 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

Regarding claims 29 and 30, the prior art of record failed to teach or suggest the claimed ratios cited as limitations to the current invention.

Regarding claims 34-36, the prior art of record failed to teach or suggest the segments of the mirror shells having different shapes.

Regarding claims 38 and 40, the prior art or record failed to teach or suggest the claimed limitations on the numerical apertures of the current invention.

Regarding claims 39 and 49, the prior art of record failed to teach or suggest the use of diaphragms in the process of EUV lithography.

Conclusion

The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.

Cole (US 4,015,120) teaches imaging rings on a detecting plate.

Levine (US 6,389,101) teaches the use of a collector in X-ray imaging.

Sweatt (US 6,469,827) teaches the use of multiple mirrors shaped into a ring in the process of EUV lithography.

Sweatt (US 6,285,737) teaches the use of multiple mirror grazing arrays in the process of EUV lithography.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Joshua L Pritchett whose telephone number is 703-305-7917. The examiner can normally be reached on Monday - Friday 7:00 - 3:30.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Cassandra Spyrou can be reached on 703-308-1687. The fax phone numbers for the organization where this application or proceeding is assigned are 703-872-9318 for regular communications and 703-872-9319 for After Final communications.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is 703-308-0956.

JLP February 13, 2003

James Phan

Primary Examiner